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(12) **United States Design Patent** (10) **Patent No.:** **US D851,140 S**
Kamimura et al. (45) **Date of Patent:** **** Jun. 11, 2019**

- (54) **PRESSING MEMBER FOR SUBSTRATE POLISHING APPARATUS**
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- (73) Assignee: **EBARA CORPORATION**, Tokyo (JP)
- (**) Term: **15 Years**
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- Aug. 5, 2016 (JP) 2016-016854
- Aug. 5, 2016 (JP) 2016-016855

- (51) **LOC (11) Cl.** **15-09**
- (52) **U.S. Cl.**
USPC **D15/126**
- (58) **Field of Classification Search**
USPC D8/70, 71; D15/126, 138
CPC B24B 9/065; B24B 21/004; B24B 37/27
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a pressing member for a substrate polishing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a first perspective view, observed from a front of a pressing member for a substrate polishing apparatus showing our new design;

FIG. 2 is a second perspective view, observed from a rear thereof;

FIG. 3 is a front view thereof;

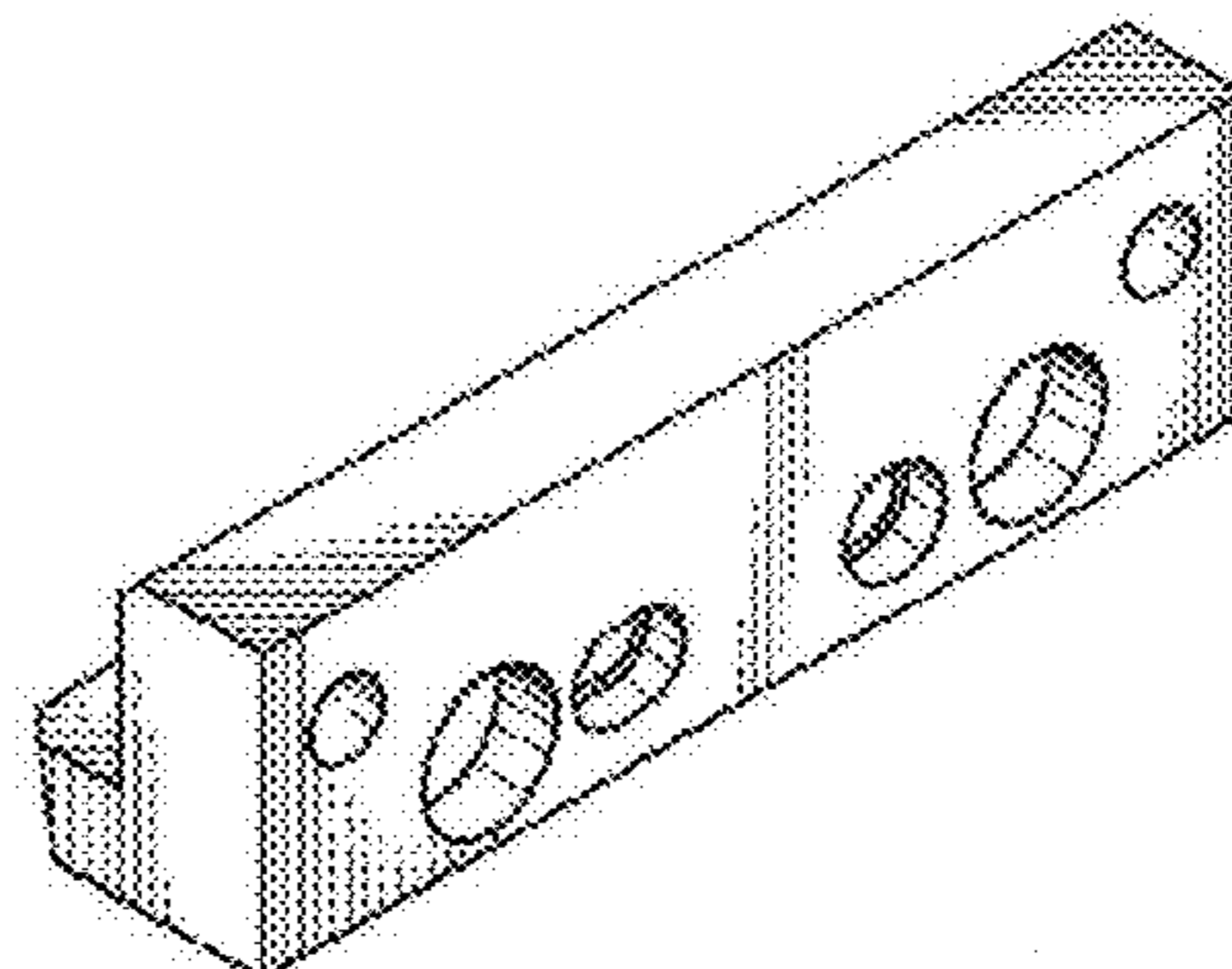
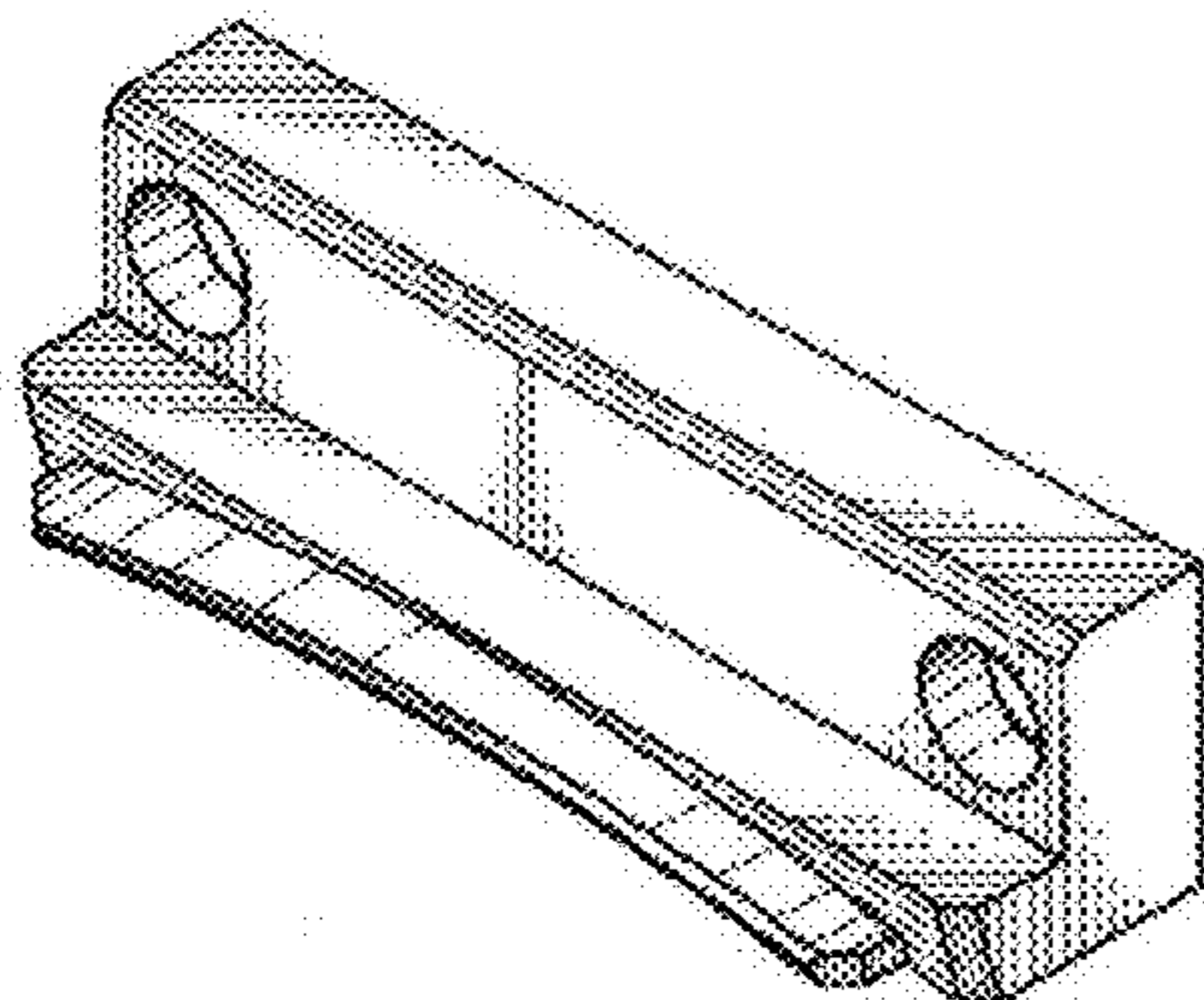
FIG. 4 is a rear view thereof;

FIG. 5 is a top view thereof;

FIG. 6 is a bottom view thereof; and,

FIG. 7 is a right-side view thereof, a left-side view being a mirror image thereof.

1 Claim, 2 Drawing Sheets



(56)

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FIG.1

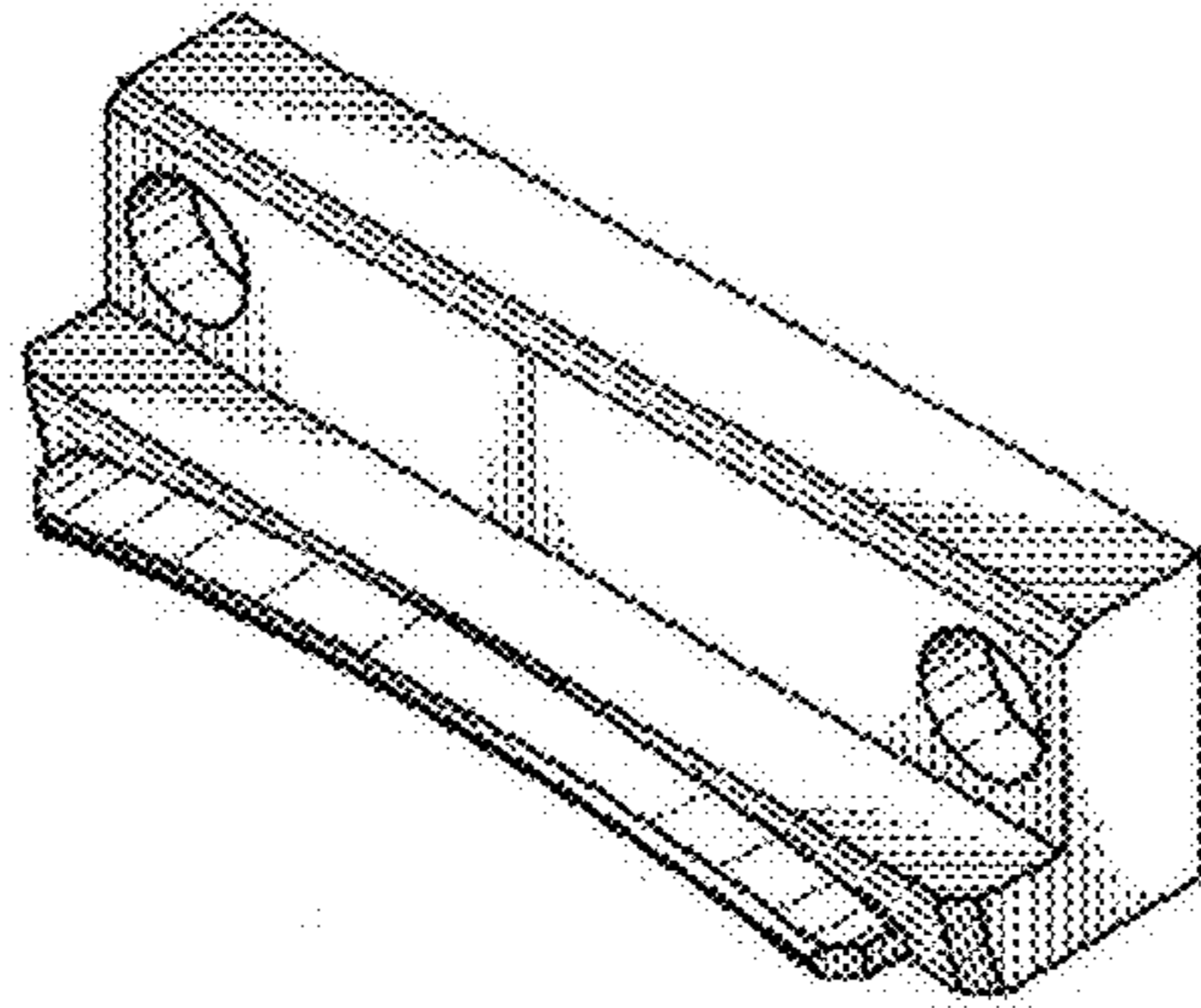


FIG.2

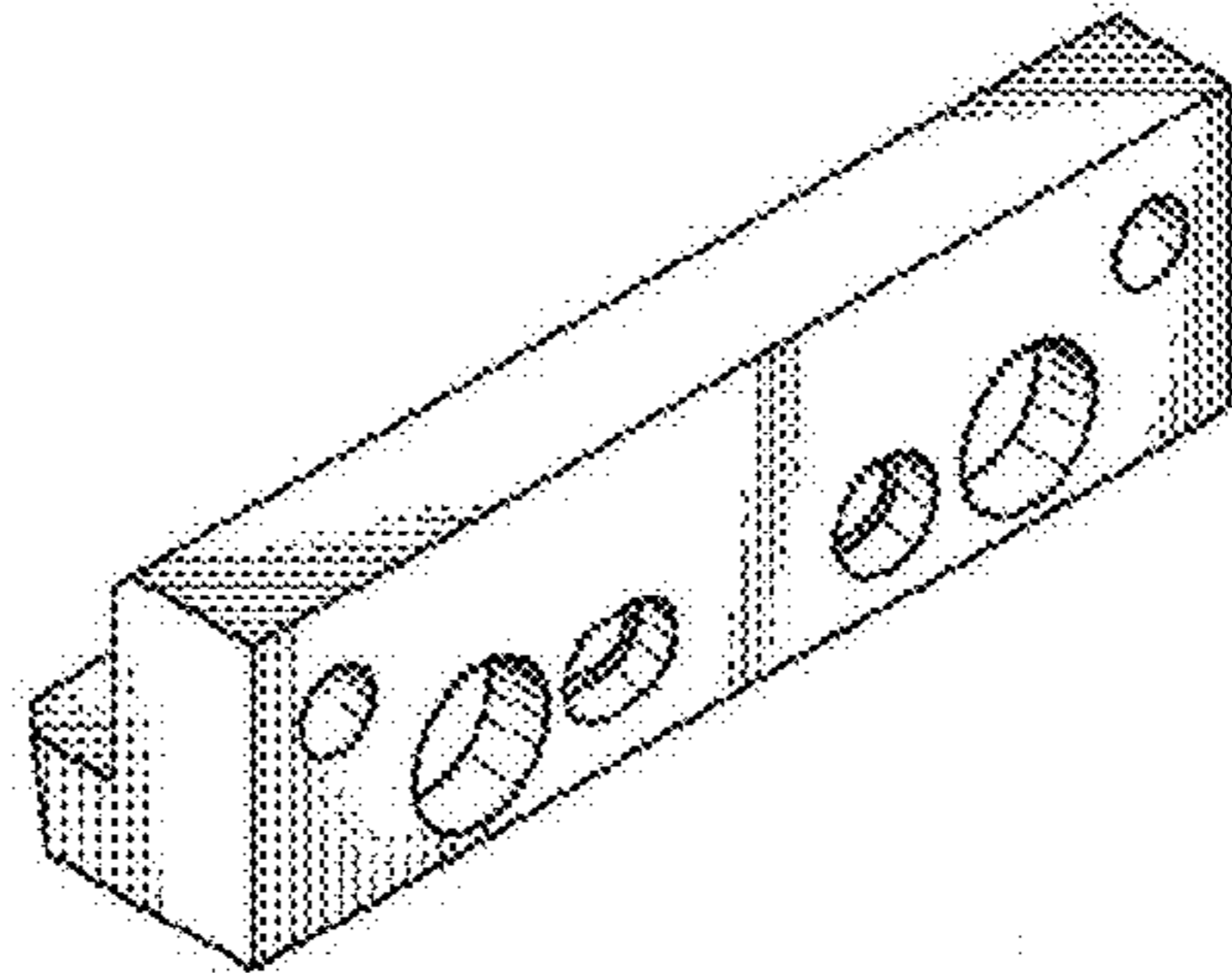


FIG.3



FIG.7

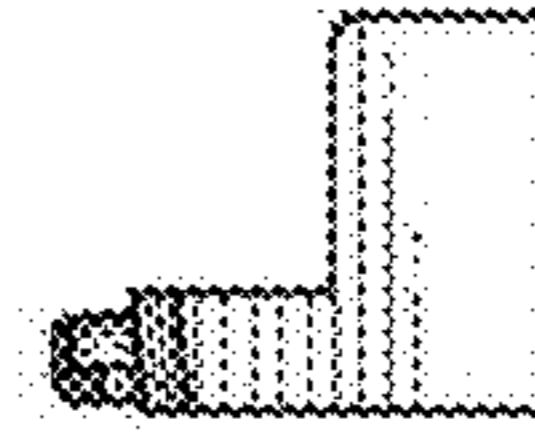


FIG.4

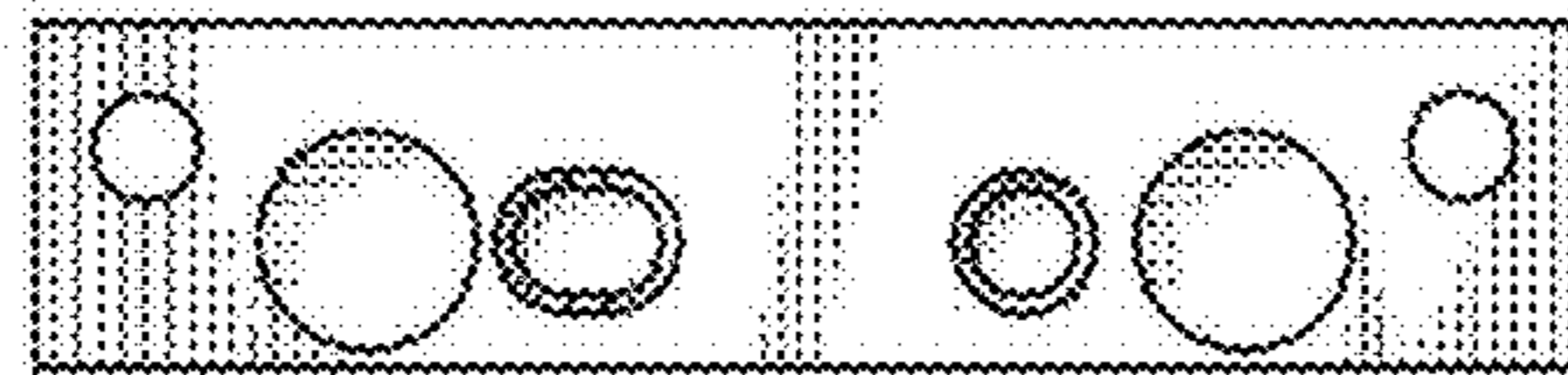


FIG.5

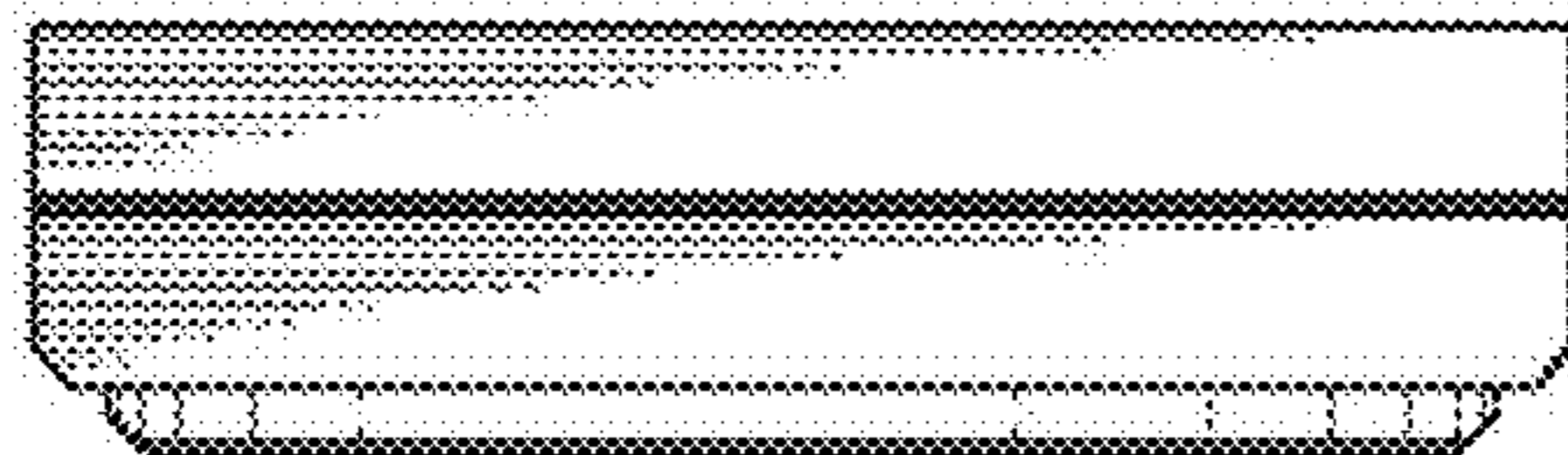


FIG.6

